

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): N. HASEGAWA, et al.
Application No.: TBD
Filed: October 17, 2003
For: MANUFACTURING METHOD OF PHOTOMASK AND
PHOTOMASK
Expected
Group: 1756
Expected
Examiner: K. Sagar

PRELIMINARY AMENDMENT

Mail Stop Patent Application
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

October 17, 2003

Sir:

Please amend the above-identified application, prior to examination thereof,
as listed in the following and as set forth on the following pages:

Amendments to the Specification;

Remarks are included following the amendments.